

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: MICHALUK *et al.*

Application No.: 09/922,815

Filed: August 6, 2001

Group Art Unit: 1742

Examiner: A. Oltmans

For: HIGH PURITY TANTALUM PRODUCTS CONTAINING THE SAME AND METHODS OF MAKING THE SAME

TC 1700 MAIL ROOM

SEP 23 2002

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AMENDMENTAssistant Commissioner for Patents  
Washington, D.C. 20231

September 20, 2002

Sir:

This Amendment is in response to the Office Action dated June 3, 2002, for which the Examiner has set a three-month period for response. A Petition for a one-month Extension of Time and the requisite fee are submitted herewith, thus making the response due on or before October 3, 2002.

Please amend the above-identified application as follows:

IN THE CLAIMS

Please substitute the following amended claims for the pending claims with the same numbers in the above-identified application. (A version of the amended claims with markings to show the changes made is also attached.)

Please cancel claims 31, 38, 40-43, 64-65, 78, 79, 80, 82, 88-92, 102, and 103 without prejudice or disclaimer of the subject matter therein.

31 1. (Amended) Tantalum metal having a purity of at least about 99.995%, and an average grain size of about 75 microns or less.

22 28. (Amended) A sputtering target comprising tantalum metal in the shape of a sputtering target having a) an average grain size of about 50 microns or less and b) a texture in

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